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Complete if Known Substitute for form 1449A/B/PTO Application Number 10/804640-Conf. #7762 **INFORMATION DISCLOSURE** Filing Date March 19, 2004 STATEMENT BY APPLICANT First Named Inventor Matthias WAGNER Art Unit 2883 (Use as many sheets as necessary) J. P. Hughes Examiner Name Sheet 1 of · 6 Attorney Docket Number 0111554.00132US3

	U.S. PATENT DOCUMENTS							
Exemin er Initials*	Cite No.1	Document Number Number-Kind Code ² (# known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear			
5 L	AA*	US-4,126,396-A	11-21-1978	Hartmann et al.				
- 17	AB*	US-4,497,544-A		Mitchell et al.				
-+-	AC*	US-4,680,085-A	07-14-1987					
-	AD*	US-4,885,622-A		Uchiyama et al.				
╅	AE*	US-4,929,063-A		Durand et al.				
+	AF*	US-5,037,169-A	08-06-1991	Chun				
+	AG.	US-5,162,239-A	11-10-1992					
	AH*	US-5,072,120-A	12-10-1991	Siewick				
	AI*	US-5,185,272-A	~~~~~~~~	Makiuchi et al.				
+	AJ*	US-5,212,584	05/1993	Chung ·				
+	AK*	US-5,218,422-A		Zoechbauer				
+	AL*	US-5,264,375-A	11-23-1993		-			
+	AM*	US-5,387,974-A	02-07-1995					
	AN*			Halbout et al.				
		US-5,408,319-A US-5,490,008-A		Guempelein et al.				
	AO*							
+	AP*	US-5,515,460-A	05-07-1996					
+	AQ*	US-5,528,071-A		Russell et al.				
	AR*	US-5,539,848-A	07-23-1996					
4-	AS*	US-5,599,403-A	02-04-1997					
+-	AT*	US-5,619,059-A	04-08-1997	Li et al.				
	AU*	US-5,694,498-A	12-02-1997	Manasson et al.				
	AV*	US-5,708,280-A	01-13-1998					
+	AW*	US-5,742,630-A	04-21-1998					
+	AX*	US-5,751,757-A	05-12-1998					
_	AY*	US-5,753,928-A	05-19-1998					
-	AZ*	US-5,767,712-A		Takemae et al.				
4-	AA1*	US-5,790,255-A		Jackson et al.				
↓_	AB1*	US-5,812,582		Gilliland et al.				
╀-	AC1*	US-5,814,871		Furukawa et al.				
↓	AD1*	US-5,940,008	02/1996	Guempelein et al.				
1_	AE1*	US-5,942,050-A	08-24-1999					
_	AF1*	US-5,953,355-A	09-14-1999					
1_	AG1*	US-6,018,421-A	01-25-2000					
	AH1*	US-6,037,644-A	03-14-2000					
	Al1*	US-6,075,647-A	06-13-2000					
	AJ1*	US-6,091,504-A		Walker et al.				
	AK1*	US-6,166,381-A	12-26-2000					
1	AL1°	US-6,180,529-B1		Gu				
	AM1"	US-6,194,721-B1	02-27-2001	Bly				
	AN1	US-6,265,242-B1		Komori et al.				
	AO1*	US-6,300,648-B1	10-09-2001	Mei et al.				
	AP1*	US-6,392,233-B1		Channin et al.				
	AQ1*	US-6,447,126-B1	09-10-2002					
	AR1*	US-6,483,862-B1		Aronson et al.				
T	AS1*	US-6,487,342	11-26-2002	Wu et al.				

Examiner	1) - 1/2	Date	
Signature	(tou files.	Considered	
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PTO/SB/08a/b (07-05)
Approved for use through 07/31/2006. OMB 0651-0031
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	100	4 7 4 4	lua a a la maa m			······
17	四		US-6,545,796-B1	04-08-2003	Greywall	
\square			US-6,670,599-A1		Wagner et al.	
Ш			US-6,737,648-B2		Fedder et al.	
\sqcup			US-6,768,097-B1		Viktorovitch et al.	
		AX1°	US-6,985,281-A1	08-14-2003	Wagner et al.	
Ш		AY1	US-09/813,447			
		AZ1	US-09/813,449			
		AA2	US-09/813,450			
\Box		AB2	US-09/813,454		Wayne et al.	
		AC2	US-09/813,455			
			US-09/813,456		Wagner, et al.	
Ш		AE2	US-09/813,462		Wagner, et al.	
Ш		AF2	US-60/480,294	06-20-2003	Wagner, et al.	
		AG2	US-60/509,379	10-07-2003	Ma, et al.	
		AH2*	US-2001/0020680	09-13-2001	Cunningham et al.	
Ш		AI2*	US-2002/0033453	03-21-2002	Sauer et al.	
Ш		AJ2*	US-2002/0080493-A1	06-27-2002	Tsai et al.	
		AK2*	US-2002/0087121	05/2003	Domash et al.	
Ш		AL2*	US-2002/0105652	08-08-2002	Domas et al.	
		AM2*	US-2002/0145139	10-10-2002	Wagner et al.	
		AN2	US-2002/172239	11-21-2002	Chapman, B.	
			US-2002/176659	11-28-2002	Colbourne et al.	
]	AP2	US-2002/181832	12-05-2002		
Ш		AQ2*	US-2002/0185588	12-12-2002	Wagner et al.	
		AR2*		12-19-2002	Seeser et al.	
\Box		AS2*	US-2003/0066967	04-10-2003	Hashimoto et al.	
		AT2*	US-2003/0072009	04-17-2003	Domash et al	
			US-2003/0087121-A1		Domash et al.	
		AV2*	US-2003/0132386	07-17-2003	Carr et al.	
		AW2°	US-2004/0104334	06-03-2004	Carr	
T		AX2*	US-2003/0141453	07-31-2003	Reed, et al.	

	FOREIGN PATENT DOCUMENTS							
Examiner	Cite	Foreign Patent Document	Publication	Name of Patentee or	Pages, Columns, Unes,	Г		
Initials*	No.	Country Code ³ -Number ⁴ -Kind Code ⁸ (# Isnown)	MM-DD-YYYY	Applicant of Cited Document	Where Relevant Passages or Relevant Figures Appear			
7	BA	EP-0125390-A1	11-21-1984	Schaumberg Hanno				
1	BB	EP-0139487	05-02-1985	Exxon Research		T		
	BC	EP-0178148-A2	04-16-1986	Xerox Corporation		Г		
	BD	EP-0518228	12-16-1992	Hartmann & Braun		П		
	BE	EP-0559347	09-08-1993	AT&T Corp.		Π		
	BF	EP-0773640	05-14-1997	AT&T		Г		
	BG	EP-0901170	03-10-1999	Sumitomo Electric Industries		П		
	ВН	EP-1055959		NEC Corporation	 	_		
	BI	EP-0859413	08-19-1998	Mitsubishi		\vdash		
	BJ	EP-0860885	08-26-1998	Canon Kabushiki Kaisha	1	Т		
	BK	EP-0883194-A1	12-09-1998	Univ Roma	†	Г		
	BL	EP-0899836-A1	03-03-1999	Xerox Corporation	 	T		
	ВМ	EP-0899835-A1	03-03-1999	Xerox Corporation	 	Г		

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S	TATEMENT	BY A	APPLICANT	First Named Inventor	Matthias WAGNER	
				Art Unit	2883	
	(Use as many sh	eets a	necessary)	Examiner Name	J. P. Hughes	
Sheet	3	of	6	Attorney Docket Number	0111554.00132US3	

7	1	BN	DE-4424717	01-19-1996	Siemens Aktiengesellschaft	
	Ī	ВО	DE-196 35 583	03-05-1998	Siemens AG	1
		BP	JP-07168040	07-04-1995	Nippon Steel Corp.	
		BQ	JP-08250551	09-27-1996	Mitsubishi Elec. Corp.	
		BR	JP-60210826	10-23-1985	Mitsubishi Elec. Corp.	
		BS	WO-89/03593	04-20-1989	Stemcor Corp.	
		BT	WO-99/30394	06-17-1999	Coherent, Inc.	
		BU	WO-00/13350	03-09-2000	E-TEK Electrophotonics Solutions Corporation	
		BV	WO-00/22479	04-20-2000	Siemens Aktiengesellschaft	
		BW	WO-00/23833	04-27-2000	Coretek Inc.	
		ВХ	WO-01/16637	03-08-2001	Epitaxx Inc.	
		BY	WO-01/67646	09-13-2001	Flanders et al	
		BZ	WO-01/73850	10-04-2001	Aegis Semiconductor Inc.	
		BA1	WO-02/50528	06-27-2002	Baltes et al.	
		BB1	WO-02/057180	07-25-2002	Honeywell International, Inc.	
	T	BC1	WO-02/103441	12-27-2002	Aegis Semiconductor Inc.	1
,	1	BD1	WO-03/046630	06-05-2003	Aegis Semiconductor Inc.	

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Examiner Initials	Cite No.1 Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), published.						
74	CA	AUGUSTINE, B.H. et al. "Thermal-optical switching of a silicon based interference filter" J. Appl. Phys. (15 February 1994): 75(04) 1875-1877					
	СВ	BAUMEISTER, P., "Simulation of a rugate filter via a stepped-index dielectric multilayer", Applied Optics, Vol. 25, No. 16, pp. 2644-2645, 1986					
CC BRUEL et al., "Smart-cut: A New Silicon on Insulator Material Technology based on Implantation and Wafer Bonding", <i>Jpn. J. Appl. Phys.</i> , Vol. 36, pp. 1636-1641, 1997							
	CD	CARBUNESCU, E. "Non linear optical effects in hydrogenated amorphous silicon" Optical Engineering, Vol. 35, No. 05, pp. 1322-1324, May 1996					
1	CE	CHOI et al. "Design and Control of a Thermal Stabilizing System for a MEMS Optomechanical Uncooled Infrared Imaging Camera", Sensors and Actuators, Vol. 203, No. A104, pp. 132-142					
1	CF	COCURULLO, G. et al. "Amorphous silicon based waveguides and light modulators for silicon low-cost photonic integrated circuits." MRS Fall Meeting Boston (December 1997)					
	CG	COCORULLO, G. et al. "Amorphous silicon waveguides and light modulators for integrated photonics realized by low-temperature plasma-enhanced chemical-vapor deposition." Optics Letters, Vol. 21, No. 4, pp. 2002-2004, 15 December 1996					
CH COCORULLO, G. et al. "Amorphous silicon-based guided-wave passive and active silicon integrated optoelectronics." <i>IEEE Jornal of Selected Topics in Quantum Ele</i> Vol. 4, No. 6, pp. 997-1002, Nov/Dec 1998 CI COCORULLO, G. et al. "Amorphous silicon waveguides and interferometers for lov silicon optoelectronics." <i>SPIE</i> , Vol. 3278, pp. 286-292, 1998							
				1 (ငၪ	CQCORULLO, G. et al., "Measurement of the thermo-optic coefficient of a-Si:H at the	

PTO/SB/08a/b (07-05)

Approved for use through 07/31/2006. OMB 0651-0031

U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE respond to a collection of information unless it contains a valid OMB control number.

Sub	stitute for form 1449A/B/PT	0		Complete if Known		
				Application Number	10/804640-Conf. #7762	
11	VFORMATION	1 DI	SCLOSURE	Filing Date	March 19, 2004	
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				Art Unit	2883	
	(Use as many sh	oets a	s necessary)	Examiner Name	J. P. Hughes	
Sheet	4	of	6	Attorney Docket Number	0111554.00132US3	

TH	4	wavelength of 1500 nm from room temperature to 200°C", Journal of Non-Crystalline Solids, pp. 310-313, 2002						
11/2	CK	COCORULLO et al., "Fast Infrared Light Modulation in a-Si:H Micro-devices", J. Non-	_					
<u> </u>		Crystalline Sol., Vol. 266, pp. 1247-1251, 2000						
1 /	CL	COCORULLO, G. et al. "Silicon thermooptical micromodulator with 700-KHz-3dB bandwidth."						
 -		IEEE Photonics Technology Letters , Vol. 7, No. 4, pp. 363-365, April 1995						
1 1	CM	COPPOLA, G. et al. "Simulation and analysis of a high-efficiency silicon optoelectronic	1					
1 1	1	modulator based on a Bragg mirror." Society of Photo-optical Instrumentation Engineers (
	-	June 2001): 40(6) 1076-1081	—					
	CN	DELLA CORTE, F. et al., "Study of the thermo-optic effect in hydrogenated amorphous silicon	1					
1 1		and hydrogenated amorphous silicon carbide between 300 and 500 K at 1.55 µm*, Applied	1					
₩	-	Physics Letters, Vol. 79, No. 2, pp. 168-170, 9 July 2001						
1 1	co	DESALVO et al., "Advanced Components and Subsystem Solutions for 40 gb/s						
\vdash		Transmission", Journal of Lightwave Technology, Vol. 20, No. 12, pp. 2175-2177, 2002						
1 1	CP	DOMASH et al., "Broadly Tunable Thin Film Interference Coatings: Active Thin Film for						
\vdash		Telecom Applications", Proceedings of SPIE, Vol. 4989, pp. 161-167, June 2003						
1	ca	DOMASH, L. et al., "Switchable thin film add/drop filter", 2003 Optical Society of America,						
$\vdash \rightarrow$	CR	PD35-1-PD25-3, 2003 DOMASH, L. et al., "Tunable thin-film filters based on thermo-optic semiconductor films",						
1	Un	DOMASH, E. et al., Tunable trin-film littles based on thermo-optic semiconductor littles,	.]					
 		Applications of Photonic Technology 5, Proceedings of SPIE, Vol. 4833, pp. 685-695, 2002						
]]	cs	DOMASH et al., "Tunable and Switchable Multiple-Cavity Thin Film Filters", Journal of						
	СТ	Lightwave Technology, Vol. 22, No. 1, pp. 126-135, 2004 EICKER, U. et al. "Optical bistability in amorphous Si-C alloys and amorphous alloy						
	انا	interference filters." Optical Society of America, Vol. 8, No. 3, pp. 614-617, 1991						
-+	cu	FERNANDES, M. et al., "VIS/NIR detector based on µc-Si:H p-I-n structures", Thin Solid						
1 1	100	Films, Elsevier Science, S.A., Vol. 364, No. 1-2, pp. 204-205, March 2000						
 -	cv	GHOSH, G., "Temperature dispersion of refractive indices in crystalline and amorphous						
lí	100	silison*, Appl. Phys. Lett. 66, Vol. 26, 26 June 1995						
\vdash	cw	GNAUCK et al., *Optical Equalization of Fiber Chromatic Dispersion in a 5-GB/S Transmission						
	1011	System', IEEE Photonics Technology Letters, Vol. 2, No. 8, pp. 585-587, 1 August 1990						
	cx	HOHLFELD et al., "A Thermally Tunable Silicon-based Optical Filter", Sensors and Actuators,						
1 !	-	Vol. 103, No. 1-2, pp. 93-99, 15 January 2003						
	CY	HOHLFELD et al., "Thermally Tunable Optical Filter Array", Proceedings of SPIE - Optical						
	1.	Devices for Fiber Communication IV, Vol. 4989, pp. 143-154, June 2003						
	cz	IODICE, M. et al. "Simple and low-cost technique for wavelength division multiplexing channel						
		monitoring.* Society of Photo-Optical Instrumentation Engineers , Vol. 69, No. 6, pp. 1704-						
		1711, June 2000						
	CA1	JABLONSKI, M. et al., "Entirely thin-film allpass coupled-cavity filters in a parallel configuration						
1 1	ı	for adjustable dispersion-slope compensation", IEEE Photonics Technology Letters, Vol. 13,						
		No. 11, November 2001						
	CB1	JDSU COADM Configurable Optical Add Drop Multiplexers,						
		http://www.jdsu.com/site/images/products/pdf/coadm_apnote, pdf						
	CC1	KAJAVA, T. et al. 'Tunable fabry-perot micro-filters for telecommunication system						
\vdash		diagnostics." Tech Dig. Conf. Lasers and Electro-Optics Cleo/Europe, p. 324, 1998						
	CD1	KOBAYASHI, Y. et al., *Improvement on Coupling Efficiency for Passive Alignment of Stacked						
		Mult-Fiber Tapes to a Vertical-Cavity Surface-Emitting Laser Array", Extend Abstracts of the						
	10=1	1996 International Conference on Solid State Devices and Materials, pp. 655-657, 1996						
	CE1	LEQUIME, M. et al., "Toward tunable thin-film filters for wavelength division multiplexing						
	1051	applications", Applied Optics, Vol. 41, No. 16, pp. 3277-3284, 1 June 2002						
<u></u>	CF1	LI, H., "Refractive Index of Silicon and Germanium and its Wavelength and Temperature						

Examiner Signature	Thre (Ma	Date Considered	3-30-09
5532495				

PTO/SB/08a/b (07-05)
Approved for use through 07/31/2006. OMB 0651-0031
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Sut	stitute for form 1449A/B/P	го		Complete if Known		
				Application Number	10/804640-Conf. #7762	
11	NFORMATION	V DI	SCLOSURE	Filing Date	March 19, 2004	
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				Art Unit	2883	
	(Use as many sh	eets as	necessary)	Examiner Name	J. P. Hughes	
Sheet	5	of	6	Attorney Docket Number	0111554.00132US3	

		Derivatives", J. Phs. and Chem. Ref. Data., Vol. 9, p. 561, 1980	
—	CG1	LUNARDI, L. et al., *Tunable dispersion compensation at 40-Gb/s using a multicavity etalon	
T/	_ 001	all-pass filter with NRZ, RZ and CS-RZ modulcation*, Journal of Lightwave Technology, Vol.	
$ \mathcal{L}_{i}^{\nu} $		20, No. 12, December 2002	
 	CH1	MADSEN et al., "A Multi-Channel Dispersion Slope Compensating Optical Allpass Filter",	
1 1	CITI		
1 1	1	Optical Fiber Communication Conference, Technical Digest Postconference edition, Vol. 2 of	
 	CI1	4, pp. WF5-1, 7 March 2000 MADSEN et al., "A Tunable Dispersion Compensating MEMS All-Pass Filter", IEEE Photonics	_
1 1	1011	Tochrology Letters Vol. 12 No. 5 pp. 651 653 2000	
-	င္သ႑	Technology Letters, Vol. 12, No. 6, pp. 651-653, 2000	
	lωι	MANDURAH, M.M., "Dopant Seregation in Polycrystalline Silicon", J. App. Phys., Vol. 51, pp.	
	CK1	5755-5763, 1980	
1 1	CKI	MARTINU, L., "Plasma deposition of optical films and coatings: A review", J. Vac. Sci.	
\vdash	CL1	Technol., Vol. 18, No. 6, pp. 2619-2645, Nov./Dec. 2000	
	CLI	MOSS et al., "Multichannel Tunable Dispersion Compensation Using all-pass Multicavity	
\vdash	0144	Etalons', Optical Society of America, 2002	
1 1	CM1	NIEMI, T. et al. "Tunable silicon etalon for simultaneous spectral filtering and wavelength	
1		monitoring of a DWDM transmitter." <i>IEEE Photoconics Technology Letters</i> (January 2001):	
\vdash	Chia	13(1) 58-60	
	CN1	ODEN et al., "Uncooled Thermal Imaging Using a Piezoresitive Microcantilever", Health	
1		Science Research Division, Oak Ridge National Laboratory, (3 pages), 1996	
1 1	CO1	PANGAL, K. et al., "Hydrogen plasma enhanced crystallization of hydrogenated amorphous	
	CP1	silicon films*, Journal of Applied Physics, Vol. 85, No. 3, pp. 1900-1906, 1 February 1999	
	CPI	PARMENTIER, R. et al., "Towards tunable optical filters", Technical Digest, OSA Topical	
	CQ1	Meeting Optical Interference Coatings, Paper WB1, 15 July 2001	
l i	CG1	PARMENTIER, R. et al., "Substrate-strain-induced tunability of dense wavelength-division multiplexing thin-film filters", Optic Letters, Vol. 28, No. 9, pp. 728-730, 1 May 2003	
\vdash	CR1	PAYNE et al., "Effects of Chlorine on Dopant Activation in α-Si:H", Appl. Phys. Lett., Vol. 76,	_
1 1	John	No. 20, p. 2949, 2000	
 	CS1	POLYAKOV et al., "Processability and Electrical Characteristics of Glass Substrates for RF	
1 1	100.	Wafer-Level Chip-Scale Packages", 2003 Proceedings 53rd, Electronic Components and	
1 1		Technology Conference, Vol. CONF. 53, 27 May 2003	
	CT1	RIANT et al., "Chirped Fiber Bragg Gratings for WDM Chromatic Dispersion Compensation in	
1	1 "	Multispan 10-Gb/s Transmission*, IEEE Journal of Selected Topics in Quantum Electronics,	
	11	Vol. 5, No. 5., pp. 1312-1323, 1999	
	1 CU1	SCHMIDT, M. A., "Wafer-to-wafer Bonding for Microstructure Formation", <i>Proc. IEEE</i> , Vol. 86,	
	11	pp. 1575-1585, 1998	
	CV1	SONG et al., "Fabrication of Single Crystalline Silicon on Glass by Smart-Cut Technique",	
	11	Chinese Physics Letters, Vol. 20, No. 1, pp. 108-110, January 2003	
	CW1	TAKAGI et al., "High-rate Growth of Stable α-Si:H", Mat. Res. Soc. Symp. Proc., Vol. 557, p.	
I = I	H^{-1}	105, 1999	
\square	CX1	TAKASHASHI, H., "Temperature stability of thin-film narrow-bandpass filters produced by ion-	
\perp /		assisted deposition, Applied Optics, Vol. 34, No. 4, pp. 667-675, 1 February 1995	
\Box	CY1	TSAI, RY. et al., "Amorphous silicon and amorphous silicon nitride films prepared by a plasma-	
\perp		enhanced chemical vapor deposition process as optical coating materials", Applied Optics,	
		Vol. 32, No. 28, pp. 5561-5566, 1 October 1993	
	CZ1	WILLNER, A., "Chromatic dispersion and polarization-mode dispersion", OPN TRENDS, pp.	
		S-16-S-21, March 2002	
	CA2	WIPIEJEWSKI et al., "Vertical-Cavity Surface-Emitting Laser Diodes for Short Distance Optical	
1	1	Fiber Networks", Proceeding of the Electronic Components and Technology Confernce,	
		Washington DC, IEEE, Vol. 44, pp. 330-334, 1994	
			

Examiner Signature	an f. m	Date Considered	3-30-06
5532495			

PTC/SB/08a/b (07-05)

Approved for use through 07/31/2006. OMB 0651-0031

U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

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				Examiner Name	J. P. Hughes
Sheet	6	of	6	Attorney Docket Number	0111554.00132US3

THE CB2	YANG et al., "Amorphous Silicon and SiGe Alloy Solar Cells Deposited by VHF", Mat. Res. Soc. Symp., Vol. 664, p. A11.3.1, 2001	
)// CC2	ZHAO et al., "Optomechanical Uncooled Infrared Imaging System: Design, Microfabrication, and Performance", Journal of Microelectromechanical Systems, Vol. 11, No. 2, pp. 136-146, 2002	

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Date Considered Examiner Signature 5532495

¹Applicant's unique citation designation number (optional). ²Applicant is to place a check mark here if English language Translation is attached.